

PHOTOSENSITIVE COMPOSITION

Patent number: JP2096755
Publication date: 1990-04-09
Inventor: NAKAI HIDEYUKI; GOTO SEI; TOMIYASU HIROSHI;
KOBAYASHI YOSHIKO
Applicant: KONISHIROKU PHOTO IND.; MITSUBISHI CHEM IND
Classification:
- international: G03F7/004; G03F7/023
- european:
Application number: JP19880249398 19881003
Priority number(s): JP19880249398 19881003

Abstract of JP2096755

PURPOSE: To obtain a photosensitive compsn. having superior capacity for forming visible picture by exposure, as well as superior under developability and high sensitivity by constituting the compsn. of 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd. an alkali soluble resin, a halomethyl oxadiazole compd., as a discoloring agent. **CONSTITUTION:** The title compsn. contains 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd., the alkali-soluble resin, the halomethyl oxadiazole compd. which generates free halogen radicals by irradiating with active light rays, and a discoloring agent which changes its tone by the interaction with a photolysis of the halomethyl oxadiazole compd. Suitable alkali-soluble resin is particularly novolak resin and vinyl polymer having structure units having phenolic OH groups in the molecule. A photosensitive planographic printing plate having superior capacity for forming visible picture by exposure, superior under developability, as well as high sensitivity, is obtd. from the above-described compsn.

Data supplied from the esp@cenet database - Worldwide

DELPHION

RESEARCH

PRODUCTS

INSIDE DELPHION



My Account

Search: Quick/Number Boolean Advanced Derwent

Help

The Delphion Integrated View

Get Now: ☒ PDF | [More choices...](#)Tools: Add to Work File: ☒ Create new Work File ☒ AddView: INPADOC | Jump to: ☒ Go to: Derwent☒ Email this to a friend

🔍 Title: **JP02096755A2: PHOTOSENSITIVE COMPOSITION**

🔍 Derwent Title: Photosensitive compsn. for lithographic plates - contg. 1,2-naphthoquinone-2-diazo-4-sulphonic acid, alkali-soluble resin, dye, and halo-methyl oxadiazole [\[Derwent Record\]](#)

🔍 Country: JP Japan

🔍 Kind: A

🔍 Inventor: NAKAI HIDEYUKI;
GOTO SEI;
TOMIYASU HIROSHI;
KOBAYASHI YOSHIKO;

🔍 Assignee: KONICA CORP
MITSUBISHI KASEI CORP
[News, Profiles, Stocks and More about this company](#)

🔍 Published / Filed: 1990-04-09 / 1988-10-03

🔍 Application Number: JP1988000249398

🔍 IPC Code: G03F 7/023; G03F 7/004;

🔍 Priority Number: 1988-10-03 JP1988000249398

🔍 Abstract: PURPOSE: To obtain a photosensitive compsn. having superior capacity for forming visible picture by exposure, as well as superior under developability and high sensitivity by constituting the compsn. of 1,2-naphthoquinone-2-diazide-4- sulfonic ester compd. an alkali soluble resin, a halomethyl oxadiazole compd., as a discoloring agent.

CONSTITUTION: The title compsn. contains 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd., the alkali-soluble resin, the halomethyl oxadiazole compd. which generates free halogen radicals by irradiating with active light rays, and a discoloring agent which changes its tone by the interaction with a photolysis of the halomethyl oxadiazole compd. Suitable alkali-soluble resin is particularly novolak resin and vinyl polymer having structure units having phenolic OH groups in the molecule. A photosensitive planographic printing plate having superior capacity for forming visible picture by exposure, superior under developability, as well as high sensitivity, is obtd. from the above-described compsn.

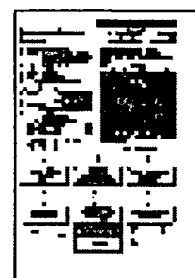
COPYRIGHT: (C)1990,JPO&Japio

🔍 INPADOC Legal Status: None [Get Now: Family Legal Status Report](#)

🔍 Designated Country: DE FR GB

🔍 Family:

PDF	Publication	Pub. Date	Filed	Title



View Image

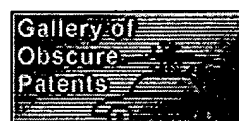
1 pag

<input type="checkbox"/>	US 9700	1993-06-15	1992-03-24	Photosensitive composition containing 1,2-naphthodione-2-diazido-4-sulfonic acid ester, alkali-soluble resin, halomethyloxadiazole compound and a dye
<input checked="" type="checkbox"/>	JP02096759A2	1990-04-09	1988-10-04	PHOTOSENSITIVE PLANOGRAPHIC PRINTING PLATE
<input checked="" type="checkbox"/>	JP02096755A2	1990-04-09	1988-10-03	PHOTOSENSITIVE COMPOSITION
<input type="checkbox"/>	EP0362778B1	1999-01-13	1989-10-02	Photosensitive composition
<input type="checkbox"/>	EP0362778A3	1991-06-12	1989-10-02	Photosensitive composition
<input type="checkbox"/>	EP0362778A2	1990-04-11	1989-10-02	Photosensitive composition
<input checked="" type="checkbox"/>	DE68928903C0	1999-02-25	1989-10-02	LICHTEMPFLINDLICHE ZUSAMMENSETZUNG
<input checked="" type="checkbox"/>	CA2000111AA	1990-04-03	1989-10-03	PHOTOSENSITIVE COMPOSITION
8 family members shown above				

Other Abstract
Info:



DERABS C90-133305



Nominate this for the Gallery...



THOMSON

Copyright © 1997-2005 The Thomson Corporati

[Subscriptions](#) | [Web Seminars](#) | [Privacy](#) | [Terms & Conditions](#) | [Site Map](#) | [Contact Us](#) | [Help](#)